

(12) INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

(19) World Intellectual Property Organization
International Bureau



(43) International Publication Date
14 December 2000 (14.12.2000)

PCT

(10) International Publication Number
WO 00/75697 A1

- (51) International Patent Classification⁷: G02B 1/02, C30B 11/00, 29/12
- (21) International Application Number: PCT/US00/14877
- (22) International Filing Date: 30 May 2000 (30.05.2000)
- (25) Filing Language: English
- (26) Publication Language: English
- (30) Priority Data:
60/137,486 4 June 1999 (04.06.1999) US
60/180,886 8 February 2000 (08.02.2000) US
60/181,338 9 February 2000 (09.02.2000) US
- (71) Applicant (for all designated States except US): CORNING INCORPORATED [US/US]; 1 Riverfront Plaza, Corning, NY 14831 (US).
- (72) Inventor; and
- (75) Inventor/Applicant (for US only): SPARROW, Robert, W. [GB/US]; 28 Woodlawn Drive, Sturbridge, MA (US).
- (54) Agent: MURPHY, Edward, F.; Corning Incorporated, Patent Dept. SP TI 3-1, Corning, NY 14831 (US).
- (81) Designated States (national): AE, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, CA, CH, CN, CU, CZ, DE, DK, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MD, MG, MK, MN, MW, MX, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TR, TT, UA, UG, US, UZ, VN, YU, ZA, ZW.
- (84) Designated States (regional): European patent (AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE).
- Published:
— With international search report.
- For two-letter codes and other abbreviations, refer to the "Guidance Notes on Codes and Abbreviations" appearing at the beginning of each regular issue of the PCT Gazette.



WO 00/75697 A1

(54) Title: FLUORIDE LENS CRYSTAL FOR OPTICAL MICROLITHOGRAPHY SYSTEMS

(57) Abstract: The present invention provides fluoride lens crystals for VUV optical lithography systems and processes. The invention provides a barium fluoride optical lithography crystal for utilization in 157 nm optical microlithography elements which manipulate below 193 nm optical lithography photons. The invention includes a barium fluoride crystalline material for use in dispersion management of below 160 nm optical lithography processes.

FLUORIDE LENS CRYSTAL FOR OPTICAL
MICROLITHOGRAPHY SYSTEMS

CROSS REFERENCE TO RELATED APPLICATIONS

5

This application claims priority to the United States Provisional Patent Application Serial No. 60/137,486, filed June 4, 1999, entitled Lenses For Optical Systems, of Robert W. Sparrow, and United States Provisional Patent Application Serial No. 60/180,886, filed February 8, 2000, entitled Lenses For Optical Systems, of
10 Robert W. Sparrow, and United States Provisional Patent Application Serial No. 60/181,338 filed February 9, 2000, entitled Lenses For Optical Systems, of Robert W. Sparrow, the content of which is relied upon and incorporated herein by reference in its entirety and the benefit of priority under 35 U.S.C. § 120 is hereby claimed.

15

BACKGROUND OF THE INVENTION

Field of the Invention

The present invention relates generally to optical lithography, and particularly to optical microlithography crystals for use in optical photolithography systems utilizing
20 vacuum ultraviolet light (VUV) wavelengths below 193 nm, preferably below 175nm, more preferably below 164 nm, such as VUV projection lithography refractive systems utilizing wavelengths in the 157 nm region.

Technical Background

Semiconductor chips such as microprocessors and DRAM's are manufactured using a technology called "Optical Lithography". An optical lithographic tool
5 incorporates an illuminating lens system for illuminating a patterned mask, a light source and a projection lens system for creating an image of the mask pattern onto the silicon substrate.

The performance of semiconductors have been improved by reducing the feature sizes. This in turn has required improvement in the resolution of the optical
10 lithographic tools. In general, the resolution of the transferred pattern is directly proportional to the numerical aperture of the lens system and inversely proportional to the wavelength of the illuminating light. In the early 1980's the wavelength of light used was 436nm from the g-line of a mercury lamp. Subsequently the wavelength was reduced to 365nm (I-line of mercury lamp) and currently the wavelength used in
15 production is 248nm obtained from the emission of a KrF laser. The next generation of lithography tools will change the light source to that of an ArF laser emitting at 193nm. The natural progression for optical lithography would be to change the light source to that of a fluoride laser emitting at 157nm. For each wavelength different materials are required to fabricate lenses. At 248nm the optical material is fused silica. For 193nm
20 systems there will be a combination of fused silica and calcium fluoride lenses. At 157nm fused silica does not transmit the laser radiation. At present the only material deemed to be useable at 157nm is calcium fluoride. See, for example, Japanese unexamined Patent Publication No. 10- 13 10 of January 6, 1998 from Application No. 8153769 filed July 14, 1996 and Japanese Patent No. 10-59799 Laid Open March 3,
25 1998 based on an application filed August 20, 1996, the Applicant in both cases being the NIKON Corporation.

Projection optical photolithography systems that utilize the vacuum ultraviolet wavelengths of light below 193 nm provide benefits in terms of achieving smaller feature dimensions. Such systems that utilize vacuum ultraviolet wavelengths in the
30 157 nm wavelength region have the potential of improving integrated circuits with smaller feature sizes. Current optical lithography systems used by the semiconductor industry in the manufacture of integrated circuits have progressed towards shorter

wavelengths of light, such as the popular 248 nm and 193 nm wavelengths, but the commercial use and adoption of vacuum ultraviolet wavelengths below 193nm, such as 157 nm has been hindered by the transmission nature of such vacuum ultraviolet wavelengths in the 157 nm region through optical materials. For the benefit of vacuum ultraviolet photolithography in the 157 nm region such as the emission spectrum VUV window of a F₂ excimer laser to be utilized in the manufacturing of integrated circuits there is a need for optical lithography crystals that have beneficial optical properties below 164 nm and at 157 nm.

The present invention overcomes problems in the prior art and provides a fluoride optical lithography crystal that can be used to improve the manufacturing of integrated circuits with vacuum ultraviolet wavelengths.

SUMMARY OF THE INVENTION

One aspect of the present invention is a below 160 nm optical lithography barium fluoride crystal. The barium fluoride crystal has a refractive index wavelength dispersion $dn/d\lambda < -0.003$ at 157 nm.

In another aspect, the present invention includes a dispersion management optical lithography crystal. The dispersion management crystal is an isotropic barium fluoride crystal. Preferably the barium fluoride crystal has a 157.6299 nm refractive index wavelength dispersion $dn/d\lambda$ less than -0.003 and a 157.6299 nm refractive index $n > 1.56$.

In a further aspect, the present invention includes a below 160 nm optical lithography method which comprises providing a below 160 nm optical lithography illumination laser, providing a calcium fluoride crystal optical element, providing a barium fluoride crystal optical element having a below 160 nm refractive index wavelength dispersion $dn/d\lambda < -0.003$, and transmitting the below 160 nm optical lithography light through the calcium fluoride optical element and the barium fluoride optical element to form an optical lithography pattern.

In another aspect, the present invention includes a method of making a dispersion managing optical lithography element. The method includes providing a barium fluoride source material, melting the barium fluoride source material to form a precrystalline barium fluoride melt, solidifying the barium fluoride melt into a barium

fluoride crystal and annealing the barium fluoride crystal to provide an isotropic barium fluoride crystal with a 157 nm refractive index wavelength dispersion $dn/d\lambda < -0.003$

Additional features and advantages of the invention will be set forth in the detailed description which follows, and in part will be readily apparent to those skilled in the art from the description or recognized by practicing the invention as described
5 herein, including the detailed description which follows and the claims.

It is to be understood that both the foregoing general description and the following detailed description are merely exemplary of the invention, and are intended to provide an overview of framework for understanding the nature and character of the
10 invention as it is claimed.

Wherein reducing the wavelength of the illuminating light for lithography processes is necessary to achieve higher resolution, the illuminating light laser emission has a finite bandwidth. To achieve the resolution required at the 100nm node, the optical lithography tool manufacturer using an all refractive optical design can either
15 use a very highly line narrowed laser (to less than 2pm) or can use two optical materials which have dispersion properties that compensate for the bandwidth of the laser.

In a preferred embodiment the invention includes providing isotropic optical lithography crystalline materials for color correction for VUV lithography in general but especially in the region of 157nm to enable refractive lenses to be constructed to
20 make use of the light from a fluoride excimer laser that has not been line narrowed to below 2pm. The invention includes a range of fluoride crystalline materials that provide benefits to 157 nm optical lithography. In the preferred embodiment the dispersion managing optical lithography crystal is utilized in conjunction with a 157 nm optical lithography illumination laser with a bandwidth not less than 0.2 picometers.

25

DETAILED DESCRIPTION OF THE PREFERRED EMBODIMENTS

The refractive index of a material varies with the wavelength of energy passing through it and this is called the dispersion of the material. Hence if light passing
30 through a lens system, constructed of one optical material, has a range of wavelengths then each wavelength would be brought to a different focus so reducing resolution. This effect can be overcome by using a second optical material with different dispersion

characteristics. This technique is known as color correction. To be of use as a color correction material, there are specific criteria that have to be met, namely the material must transmit at the wavelength of operation, it must be isotropic and must have optimum dispersion characteristics. At 157nm, the only material that has had its dispersion characteristics measured to the necessary degree of accuracy is calcium fluoride. Applying the criteria of 157nm transmission and of being isotropic, the following materials can be used as color correction materials.

I. Materials based on alkali metal fluorides:

Lithium fluoride, sodium fluoride, potassium fluoride, and materials of the formula: MRF_3 in which M is either Li, Na or K and R is either Ca, Sr, Ba or Mg. Examples of such materials include but are not limited to: KMgF_3 , KSrF_3 , KBaF_3 , KCaF_3 , LiMgF_3 , LiSrF_3 , LiBaF_3 , LiCaF_3 , NaMgF_3 , NaSrF_3 , NaBaF_3 , and NaCaF_3 .

II. Materials based on alkaline earth metal fluorides:

Calcium fluoride, barium fluoride and strontium fluoride. Each of these materials can be combined with the other to form a mixed crystal of the formula $(\text{M1})_x(\text{M2})_{1-x}\text{F}_2$ in which M1 is either Ba, Ca or Sr and M2 is either Ba, Ca or Sr and x is an quantity between 0 and 1. Non-limiting examples are $\text{Ba}_{0.5}\text{Sr}_{0.5}\text{F}_2$ in which $x = 0.5$ and $\text{Ba}_{0.25}\text{Sr}_{0.75}\text{F}_2$, in which $x = 0.75$. When $x = 0$, the materials are CaF_2 , BaF_2 , SrF_2

III. Materials based on mixed crystals of the formula $\text{M}_{1-x}\text{R}_x\text{F}_{2+1}$, in which M is either Ca, Ba or Sr and R is lanthanum.

In such materials the structure of the crystal is isotropic up to x values of 0.3. Examples of this formula include but are not limited to $\text{Ca}_{0.72}\text{La}_{0.28}\text{F}_{2.28}$ in which $x = 0.28$ or $\text{Ba}_{0.74}\text{La}_{0.26}\text{F}_{2.26}$ in which $x = 0.26$ or of the type $\text{Sr}_{0.79}\text{La}_{0.21}\text{F}_{2.21}$ in which $x = 0.21$.

Each of the above materials I. II and III can be manufactured using a technique known as the "Stockbarger" or "Bridgman" technique of crystal growth. This process

comprises loading the powder of the material to be grown into a container known as a crucible. The crucible which usually is made of high purity graphite is positioned on a moveable support structure within a heater with sufficient power to raise the temperature to a level above the melting point of the material to be grown. After assembling the heater system around the crucible, the system is closed with a bell jar and evacuated using a combination of vacuum pumps. After a vacuum exceeding 10^{-5} Torr has been achieved, power is applied to the heater and is continually raised until a preset level has been achieved. This preset level of power is defined by melt trial runs. After a period of several hours at the melt power, the moveable support structure is activated and the crucible is made to slowly descend in the furnace. As the tip of the crucible descends, it cools and the molten material begins to freeze. By continuing the descent there is progressive solidification until all the melt is frozen. At this point, the power to the furnace is reduced to below the melt power, the crucible is raised back into the heater, allowed to reach thermal equilibrium over a period of several hours and then allowed to cool to room temperature by slowly reducing the power to the heaters. Once at room temperature, the vacuum is released, the bell jar removed followed by the heaters and the crystal can be removed from the crucible.

Although the Bridgman or Stockbarger method of crystal growth is the usual method of growing crystals of fluoride based materials, it is not the only method available. Techniques such as the Czochralski, Kyropoulos or Stober methods can also be utilized.

The size and shape of the disks resulting from these materials are variable e.g. for lenses: 118-250 mm in diameter by 30-50 mm in thickness. The disks are ground in a conventional manner to lenses of about the same dimensions and having the desired curvature. The lenses have a general application, for example, whenever color correction is required. The lenses can then be incorporated in a wide variety of optical systems, e.g. lasers including but limited to the 157nm systems, spectrography systems, microscopes and telescopes.

The preceding specific embodiments are to be construed as merely illustrative, and not limitative of the remainder of the disclosure in any way whatsoever.

The entire disclosure of all applications, patents and publications, cited above and below, are hereby incorporated by reference.

From the foregoing description one skilled in the art can easily ascertain the essential characteristics of this invention, and without departing from the spirit and scope thereof, can make various changes and modifications of the invention to adapt it to various usages and conditions.

5 The invention includes a below 160 nm optical crystal transmitting for use with a below 160 nm lithography laser having a bandwidth of at least .2 pm. The optical lithography crystal is comprised of an isotropic barium fluoride crystal which has a 157 nm transmission greater than 85% and a refractive index wavelength dispersion $dn/d\lambda < -0.003$ at 157 nm. Preferably the barium fluoride crystal has a 157 nm, refractive index
10 wavelength dispersion $dn/d\lambda < -0.004$, and more preferably < -0.0043 . Preferably the barium fluoride crystal has a 157 nm refractive index $n > 1.56$. More preferably $n \geq 1.6$, and most preferably $n \geq 1.64$. Preferably the barium fluoride crystal has a 157 nm refractive index temperature coefficient $dn/dt > 8 \times 10^{-6}/^{\circ}\text{C}$, and more preferably $dn/dt \geq 8.5 \times 10^{-6}/^{\circ}\text{C}$. In a preferred embodiment the optical lithography barium
15 fluoride crystal has a large dimension diameter > 100 mm and a thickness > 30 mm, and more preferably a diameter in the range of about 118 to 250 mm and a thickness in the range of about 30 to 50 mm. When utilized with a broadband width illumination source such as an F_2 excimer laser with a bandwidth of at least .5 pm, said barium fluoride crystal comprises a bandwidth dispersion managing optical element.
20 Preferably the barium fluoride optical lithography crystal has a sodium contamination content < 10 ppm by weight, more preferably < 5 ppm by weight, and most preferably < 1 ppm. Preferably the barium fluoride optical lithography crystal has a total rare earth contaminant content of less than 1 ppm by weight. Preferably the barium fluoride optical lithography crystal has a total oxygen contaminant content of less than 50 ppm
25 by weight, and more preferably < 20 ppm. Such low contaminant levels provide beneficial optical characteristics, and preferably the crystal has a 157 nm transmission $\geq 86\%$, and more preferably $\geq 88\%$.

 In a further aspect the invention includes a below 160 nm dispersion management optical lithography crystal. The dispersion management optical
30 lithography crystal comprises an isotropic barium fluoride crystal having a 157.6299 nm refractive index wavelength dispersion $dn/d\lambda < -0.003$ and a 157.6299 nm refractive

index $n > 1.56$. Preferably the dispersion management crystal's $dn/d\lambda < -0.004$, and more preferably $dn/d\lambda < -0.0043$. Preferably the crystal's refractive index $n > 1.6$.

In a further aspect the invention includes a below 160 nm optical lithography method which includes providing a below 160 nm optical lithography illumination
5 laser, providing a calcium fluoride crystal optical element, and providing a barium fluoride crystal optical element having a below 160 nm refractive index wavelength dispersion $dn/d\lambda$ which is < -0.003 . The method includes transmitting below 160 nm optical lithography light through the calcium fluoride optical element and the barium fluoride optical element to form an optical lithography pattern, preferably with feature
10 dimensions ≤ 100 nm. Providing the barium fluoride crystal optical element preferably includes loading a barium fluoride crystal feedstock into a container, melting the feedstock to form a precrystalline barium fluoride melt, and progressively freezing the barium fluoride melt into a barium fluoride crystal. The method preferably further includes heating the barium fluoride crystal and slowly thermal equilibrium cooling the
15 crystal and forming the barium fluoride crystal into an optical element. Preferably the illumination laser has a bandwidth $\geq .5$ pm, and preferably ≥ 1 pm. In another aspect the invention includes the method of making a dispersion managing optical lithography element. The method includes providing a barium fluoride source material, melting the barium fluoride source material to form a precrystalline barium fluoride melt, solidifying
20 the barium fluoride melt into a barium fluoride crystal, and annealing the barium fluoride crystal to provide an isotropic barium fluoride crystal with a 157 nm refractive index wavelength dispersion $dn/d\lambda < -0.003$. The method preferably includes providing a contaminant removing fluoride scavenger and melting the scavenger with the barium fluoride source material to remove contaminants. Preferably the scavenger
25 is lead fluoride.

Example

Barium fluoride optical lithography crystal samples were produced. 157 nm range refractive index measurements were made on a produced crystal. 157 nm range
30 transmission exposures were made on a produced crystal.

Crystals were grown in high purity graphite crucible containers. High purity barium fluoride powder was loaded into the crucible. The loaded crucible was positioned on a movable support structure within a crystal growing heater device with sufficient power to raise the temperature to a temperature above 1280 °C. The barium fluoride powder was melted above 1280°C into a precrystalline barium fluoride melt, then the crucible was lowered through a 1280°C containing thermal gradient to progressively freeze solidify the melt into a crystalline form. The formed crystal was then annealed by heating to a temperature below 1280°C and then slowly cooling to allow the barium fluoride crystal to reach thermal equilibrium and reduce stress and birefringence of the crystal. Such formed barium fluoride crystal samples were then analyzed. A 157 nm transmission laser durability sample showed an external transmission of 86%. A 157 nm absolute refractive index sample showed a 157 nm dispersion at 20°C of $dn/d\lambda$ (157.6299) = $-0.004376 \pm 0.000004 \text{ nm}^{-1}$ with the absolute refractive index at the 157 nm wavelength of 157.6299, $n(\lambda = 157.6299) = 1.656690 \pm 0.000006$, and also the refractive index temperature coefficient about 20°C was found to be dn/dT (approx. 20°C, 1 atmosphere N_2) = $10.6 (\pm 0.5) \times 10^{-6}/^\circ\text{C}$ and dn/dT (approx. 20°C, vacuum) = $8.6 (\pm 0.5) \times 10^{-6}/^\circ\text{C}$.

It will be apparent to those skilled in the art that various modifications and variations can be made to the present invention without departing from the spirit and scope of the invention. Thus, it is intended that the present invention cover the modifications and variations of this invention provided they come within the scope of the appended claims and their equivalents.

CLAIMS:

1. A below 160 nm optical lithography crystal, said optical lithography crystal comprised of a barium fluoride crystal, said barium fluoride crystal having a 157 nm
5 transmission > 85%, said crystal having a refractive index wavelength dispersion $dn/d\lambda$ < -0.003 at 157 nm.
2. An optical lithography crystal as claimed in claim 1, wherein said dispersion $dn/d\lambda$ < -0.004.
- 10 3. An optical lithography crystal as claimed in claim 1, wherein said dispersion $dn/d\lambda$ < -0.0043.
4. An optical lithography crystal as claimed in claim 1, wherein said barium
15 fluoride crystal has a 157 nm refractive index $n > 1.56$.
5. An optical lithography crystal as claimed in claim 1, wherein said barium fluoride crystal has a 157 nm refractive index $n > 1.6$.
- 20 6. An optical lithography crystal as claimed in claim 1, wherein said barium fluoride crystal has a 157 nm refractive index $n > 1.64$.
7. An optical lithography crystal as claimed in claim 1, wherein said barium fluoride crystal has a 157 nm refractive index temperature coefficient $dn/d\lambda > 8 \times 10^{-6}/^{\circ}\text{C}$.
25 $^{\circ}\text{C}$.
8. An optical lithography crystal as claimed in claim 1 having a large dimension diameter > 100 mm and a thickness > 30 mm.
- 30 9. An optical lithography crystal as claimed in claim 1 having a diameter in the range of about 118 to 250 mm and a thickness in the range of about 30 to 50 mm.

10. An optical lithography crystal as claimed in claim 1, wherein said crystal comprises a bandwidth dispersion managing optical element.
- 5 11. An optical lithography crystal as claimed in claim 1, wherein said barium fluoride crystal has a sodium content < 10 ppm by weight.
12. An optical lithography crystal as claimed in claim 1, wherein said barium fluoride crystal has a total rare earth contaminant content of less than 1 ppm by weight.
- 10 13. An optical lithography crystal as claimed in claim 1, wherein said barium fluoride crystal has an oxygen contaminant content of less than 50 ppm by weight.
14. An optical lithography crystal as claimed in claim 1, wherein said barium fluoride crystal has an oxygen contaminant content of less than 20 ppm by weight.
- 15 15. An optical lithography crystal as claimed in claim 1, wherein said barium fluoride crystal has a 157 nm transmission $\geq 86\%$.
- 20 16. An optical lithography crystal as claimed in claim 1, wherein said barium fluoride crystal has an oxygen contaminant content of less than 20 ppm by weight, a 157 nm transmission $\geq 86\%$.
- 25 17. A dispersion management optical lithography crystal comprised of an isotropic barium fluoride crystal, said barium fluoride crystal having a 157.6299 nm refractive index wavelength dispersion $dn/d\lambda < -0.003$ and a 157.6299 nm refractive index $n > 1.56$.
- 30 18. A dispersion management crystal as claimed in claim 17 wherein $dn/d\lambda < -0.004$.

19. A dispersion management crystal as claimed in claim 17 wherein $dn/d\lambda < -0.0043$.
20. A dispersion management crystal as claimed in claim 17 wherein said refractive
5 index $n > 1.6$.
21. A dispersion management crystal as claimed in claim 17 wherein said crystal has a measured external 157 nm transmissions $> 83\%$.
- 10 22. A dispersion management crystal as claimed in claim 17 wherein said crystal has a measured external 157 nm transmission $\geq 85\%$.
23. A below 160 nm optical lithography method comprised of
providing a below 160 nm optical lithography illumination laser,
15 providing a calcium fluoride crystal optical element,
providing a barium fluoride crystal optical element, said barium fluoride crystal element having a below 160 nm refractive index wavelength dispersions $dn/d\lambda < -0.003$,
transmitting below 160 nm optical lithography light through said calcium
20 fluoride optical element and said barium fluoride optical element to form an optical lithography pattern.
24. A method as claimed in claim 23 wherein providing a barium fluoride crystal optical element includes:
25 loading a barium fluoride crystal feedstock into a container,
melting said barium fluoride crystal feedstock to form a precrystalline barium fluoride melt,
progressively freezing said barium fluoride melt into a barium fluoride crystal,
heating said barium fluoride crystal and thermal equilibrium cooling said
30 crystal,
forming said barium fluoride crystal into an optical element.

25. A method of making a dispersion managing optical lithography element, said method comprising:
- providing a barium fluoride source material,
 - melting said barium fluoride source material to form a precystalline barium fluoride melt,
 - solidifying said barium fluoride melt into a barium fluoride crystal,
 - annealing said barium fluoride crystal to provide an isotropic barium fluoride crystal with a 157 nm refractive index wavelength dispersion $dn/d\lambda < -0.003$.
26. A method as claimed in claim 25 which includes providing a contaminant removing fluoride scavenger and melting the scavenger with the barium fluoride source material to remove contaminants.
27. A method of making a dispersion managing optical lithography crystal for color correcting calcium fluoride at 157 nm, said method comprising:
- providing a fluoride color correction material,
 - melting said fluoride color correction material to form a precystalline fluoride color correction material melt,
 - solidifying said fluoride color correction material melt into a color correction material fluoride crystal,
 - annealing said color correction material fluoride crystal to provide an isotropic color correction material fluoride crystal with a 157 nm refractive index wavelength dispersion $dn/d\lambda < -0.003$ and a 157 nm transmission $> 80\%$.

INTERNATIONAL SEARCH REPORT

Inte. l. onal Application No

PCT/US 00/14877

A. CLASSIFICATION OF SUBJECT MATTER
IPC 7 G02B1/02 C30B11/00 C30B29/12

According to International Patent Classification (IPC) or to both national classification and IPC

B. FIELDS SEARCHED

Minimum documentation searched (classification system followed by classification symbols)

IPC 7 C30B G02B

Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched

Electronic data base consulted during the international search (name of data base and, where practical, search terms used)

PAJ, WPI Data, EPO-Internal

C. DOCUMENTS CONSIDERED TO BE RELEVANT

Category *	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
E	EP 1 006 373 A (ZEISS CARL ;ZEISS STIFTUNG (DE)) 7 June 2000 (2000-06-07) page 6, line 19 - line 45; figure 1 ---	1-7,23
X	DD 222 426 A (VEB CARL ZEISS) 28 September 1988 (1988-09-28) page 2, line 25 - line 36 ---	1
A	JIANG: "growth and properties of scintillating crystal BaF2" JOURNAL OF CRYSTAL GROWTH., vol. 79, no. 1-3, December 1986 (1986-12), pages 720-722, XP002146967 NORTH-HOLLAND PUBLISHING CO. AMSTERDAM., NL ISSN: 0022-0248 page 720 -page 721 --- -/-	23,24

☒ Further documents are listed in the continuation of box C.

☒ Patent family members are listed in annex.

* Special categories of cited documents :

"A" document defining the general state of the art which is not considered to be of particular relevance

"E" earlier document but published on or after the international filing date

"L" document which may throw doubts on priority claim(s) or which is cited to establish the publication date of another citation or other special reason (as specified)

"O" document referring to an oral disclosure, use, exhibition or other means

"P" document published prior to the international filing date but later than the priority date claimed

"T" later document published after the international filing date or priority date and not in conflict with the application but cited to understand the principle or theory underlying the invention

"X" document of particular relevance; the claimed invention cannot be considered novel or cannot be considered to involve an inventive step when the document is taken alone

"Y" document of particular relevance; the claimed invention cannot be considered to involve an inventive step when the document is combined with one or more other such documents, such combination being obvious to a person skilled in the art.

"&" document member of the same patent family

Date of the actual completion of the international search

11 September 2000

Date of mailing of the international search report

25/09/2000

Name and mailing address of the ISA

European Patent Office, P.B. 5818 Patentlaan 2
NL - 2280 HV Rijswijk
Tel. (+31-70) 340-2040, Tx. 31 651 epo nl.
Fax: (+31-70) 340-3016

Authorized officer

Cook, S

INTERNATIONAL SEARCH REPORT

International Application No

PCT/US 00/14877

C.(Continuation) DOCUMENTS CONSIDERED TO BE RELEVANT

Category	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
A	EP 0 875 778 A (NIPPON KOGAKU KK) 4 November 1998 (1998-11-04) page 12 -page 13 ---	1-27
A	PATENT ABSTRACTS OF JAPAN vol. 1998, no. 08, 30 June 1998 (1998-06-30) & JP 10 059799 A (NIKON CORP), 3 March 1998 (1998-03-03) cited in the application abstract -----	

INTERNATIONAL SEARCH REPORT

Information on patent family members

Int. .onal Application No

PCT/US 00/14877

Patent document cited in search report	Publication date	Patent family member(s)	Publication date
EP 1006373 A	07-06-2000	DE 19929701 A EP 1006388 A JP 2000171707 A	31-05-2000 07-06-2000 23-06-2000
DD 222426 A	15-05-1985	DD 222426 B	13-06-1996
EP 0875778 A	04-11-1998	JP 10260349 A US 6061174 A	29-09-1998 09-05-2000
JP 10059799 A	03-03-1998	NONE	